

Interference Search

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	941	((high adj density adj plasma) or HDP) near15 (oxide or SiO2 or SiO?sub\$3)).clm.	US-PGPUB; USPAT	OR	ON	2005/09/30 13:19
L2	30896	(CMP or polish\$6).clm.	US-PGPUB; USPAT	OR	ON	2005/09/30 13:19
L3	415	1 and 2	US-PGPUB; USPAT	OR	ON	2005/09/30 13:19
L4	147	3 and (stop\$6 or polishstop or etchstop).clm.	US-PGPUB; USPAT	OR	ON	2005/09/30 13:20
L5	136	4 and (conductive or polysilicon or silicon or Si or polySi).clm.	US-PGPUB; USPAT	OR	ON	2005/09/30 13:21
L6	47	5 and ((planar\$6 or flat\$6) near5 (surface or region or area)).clm.	US-PGPUB; USPAT	OR	ON	2005/09/30 13:22